

Abstract

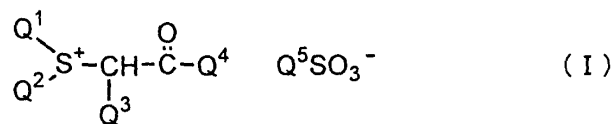
The present invention provides a positive resist composition comprising

(A) a resin which itself is insoluble or poorly soluble in an alkali aqueous

5 solution but becomes soluble in an alkali aqueous solution by the action of an acid, wherein the content of halogen atoms in the resin is 40% by weight or more, at least one of structural units constituting the resin is a structural unit having an alicyclic hydrocarbon skeleton, and the structural unit having an alicyclic hydrocarbon skeleton contains therein at least one group rendering the resin

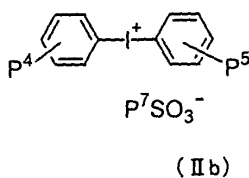
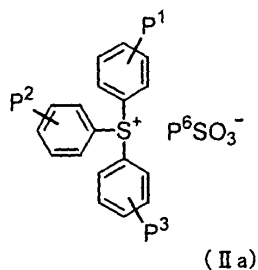
10 soluble in an alkali aqueous solution by the action of an acid, and at least one halogen atom, and a carbon in the alicyclic hydrocarbon skeleton may be substituted by an oxygen, and

(B) (a) an acid generator comprising a sulfonium salt of the formula (I)



15 wherein Q^1 , Q^2 , Q^3 and Q^4 are defined in the specification, and

(b) a triphenylsulfonium salt of the formula (IIa) and/or a diphenyliodonium salt of the formula (IIb)



wherein P^1 , P^2 , P^3 , P^4 , P^5 , P^6SO_3^- and P^7SO_3^- are defined in the specification.